IN THE CLAIMS:

Please amend claim 23, 24, and 26, as follows:

- (Previously Amended) An electrode comprising:
 - a heater arranged on a plane;
- an upper ceramic-metal composite arranged above the heater; and an lower ceramic-metal composite arranged below the heater, wherein the heater and the upper and lower ceramic-metal composites are cast in a base metal.
- 2. (Previously Amended) An electrode comprising:
 - a heater arranged on a plane; and
 - a core metal plate arranged substantially parallel to the plane and adjacent to the heater;

wherein the heater and the core metal are cast in a base metal.

- (Previously Amended) The electrode according to claim 2, wherein the core metal plate comprises a plurality of base metal communication holes.
- 4. (Previously Amended) The electrode according to claim 2, wherein a lower surface of the base metal is configured to adopt a shower head portion that supplies a gas.
- 5. (Previously Amended) The electrode according to claim 2, wherein the electrode is configured so that a high frequency voltage is applied thereto.
- 6. (Previously Amended) A susceptor comprising:
 - a heater arranged on a plane;
 - an upper ceramic-metal composite arranged above the heater;

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an lower ceramic-metal composite arranged below the heater; and a ceramic electrostatic chuck for holding an object to be treated, the electrostatic chuck having a coefficient of linear thermal expansion substantially the same as that of the upper ceramic-metal composite, and being joined to an upper surface of the upper ceramic-metal composite.

- 7. (Previously Amended) The susceptor according to claim 6, wherein the heater and the upper and lower ceramic-metal composites are cast in a base metal.
- 8. (Previously Amended) The susceptor according to claim 6, wherein the upper ceramic-metal composite and the electrostatic chuck are brazed together.
- 9. (Previously Amended) The susceptor according to claim 6, wherein the upper ceramic-metal composite and the electrostatic chuck are forge-welded together.
- 10. (Previously Amended) The susceptor according to claim 6, wherein the upper ceramic-metal composite and the electrostatic chuck are adhered together.
- 11. (Previously Amended) The susceptor according to claim 6, wherein the susceptor is configured so that a high frequency voltage is applied thereto.
- 12. (Previously Amended) A plasma processing apparatus comprising:

a processing vessel;

an electrode including:

a heater arranged on a plane;

an upper ceramic-metal composite arranged above the heater; and an lower ceramic-metal composite arranged below the heater,

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wherein the heater and the upper and lower ceramic-metal composites are cast in a base metal; and a high frequency power source that applies a high frequency voltage to

13. (Previously Amended) A plasma processing apparatus comprising:

a processing vessel,

the electrode.

an electrode including:

a heater arranged on a plane; and

a core metal plate arranged substantially parallel to the plane and adjacent to the heater;

wherein the heater and the ceramic-metal composites are cast in a base metal; and

a high frequency power source that applies a high frequency voltage to the electrode.

- 14. (Previously Amended) The apparatus according to claim 13, wherein the core metal plate comprises a plurality of base metal communication holes.
- 15. (Previously Amended) The plasma processing apparatus according to claim 12, wherein a lower surface of the base metal is configured to adopt a shower head portion that supplies a gas.
- 16. (Previously Amended) A plasma processing apparatus comprising:
 - a processing vessel,
 - a susceptor including:
 - a heater arranged on a plane;

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an upper ceramic-metal composite arranged above the heater; and lower ceramic-metal composite arranged below the heater; and a ceramic electrostatic chuck for holding an object to be treated, the electrostatic chuck having a coefficient of linear thermal expansion substantially the same as that of the upper ceramic-metal composite, and being joined to an upper surface of the upper ceramic-metal composite; and

a high frequency power source that applies a high frequency voltage to the susceptor.

- 17. (Original) The plasma processing apparatus according to claim 16, wherein the heater and the upper and lower ceramic-metal composites are cast in a base metal.
- 18. (Previously Amended) The plasma processing apparatus according to claim 16, wherein the susceptor is provided with at least one heat transfer gas passage for supplying a heat transfer gas to a surface of the electrostatic chuck.
- 19. (Previously Amended) The plasma processing apparatus according to claim 16, wherein the upper ceramic-metal composite and the electrostatic chuck are brazed together.
- 20. (Previously Amended) The plasma processing apparatus according to claim 16, wherein the upper ceramic-metal composite and the electrostatic chuck are forge-welded together.

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- 21. (Previously Amended) The plasma processing apparatus according to claim 16, wherein the upper ceramic-metal composite and the electrostatic chuck are adhered together.
- 22. (Previously Amended) A method of making an electrode, comprising:

placing a heater and a pair of porous ceramics in a mold with a positional relationship where the pair of porous ceramics are arranged above and below the heater respectively so that the heater is positioned therebeween; and

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- pouring a molten base metal into the mold to cast the pair of porous ceramics and the heater in the base metal, thereby infiltrating the porous ceramic with the base metal in order to form a ceramic-metal composite.
- 23. (Currently Amended) A method of making a susceptor, comprising:
 - placing a heater and a pair of porous ceramics in a mold with a positional relationship where the pair of porous ceramics are arranged above the and below the heater respectively so that the heater is positioned therebeween; and
 - pouring a molten base metal into the mold to cast the pair of porous ceramics and the heater in the base metal, thereby infiltrating the porous ceramic with the base metal in order to form a ceramic-metal composite.

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- 24. (Currently Amended) The plasma processing apparatus electrode according to claim 1, wherein a lower surface of the base metal is configured to adopt a shower head portion that supplies a gas.
- 25. (Previously Amended) The electrode according to claim 1, wherein the electrode is configured so that a high frequency voltage is applied thereto.
- 26. (Currently Amended) The electrode plasma processing apparatus according to claim 13, wherein a lower surface of the base metal is configured to adopt a shower head portion that supplies a gas.

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